

放射光アブレーションによるフラーレン薄膜の作製

Deposition of Fullerene Thin Films Using Synchrotron Radiation Ablation

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Abstract

Fullerene thin films were deposited on Si substrates using synchrotron radiation ablation at room temperature. The deposited films were characterized by X-ray diffraction, Fourier-transform infrared spectroscopy and Raman spectroscopy. X-ray diffraction patterns indicate that the crystalline fullerene film was obtained by room temperature deposition.

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